# A 60-GHz Transmission Line Phase Shifter Using Varactors and Tunable Inductors in 65-nm CMOS Technology 

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#### Abstract

This paper describes a $\mathbf{6 0 - G H z}$ artificial transmission line phase shifter designed in $65-\mathrm{nm}$ CMOS technology. To increase the phase shift range and preserve the matching over the entire phase shift range, the fixed series inductors in the standard line cell are substituted by tunable inductors. The required tunable inductors are constructed using a transformer with the transformer secondary loaded by a varactor. To verify the operation principle, the phase shifters, including one-, two- and three-cell, are manufactured. The experimental phase shift range is $45^{\circ}$ for one-cell, $92^{\circ}$ for two-cell, and $133^{\circ}$ for three-cell line shifters. These figures are nearly $\mathbf{8 0 \%}$ larger than the corresponding phase shifts in the lines consisting of cells with fixed inductors. The input/output return loss is less than 10 dB for all cases over the entire phase shift range. The average insertion loss is 3.2 dB for one-cell, 5.6 dB for two-cell, and 7.8 dB for three-cell transmission line phase shifters. The proposed continuous phase shifter achieves the highest phase shift range per area among the millimeter-wave transmission line and switch-type phase shifters reported to date.


Index Terms-CMOS integrated circuits, millimeter-wave (mm-wave) silicon RFICs, phase shifters, phased arrays, varactors.

## I. Introduction

EVER increasing demand for high-definition high-datarange wireless communication can only be met by the development of wireless communication systems at millimeter-wave (mm-wave) frequencies and beyond because of bandwidth scarcity in crowded low-gigahertz frequencies. With its 7 GHz of unlicensed bandwidth, the $60-\mathrm{GHz}$ band offers the required bandwidth and great interoperability for development of such high-data-rate wireless communication channels especially gigabit per second wireless networking applications [1]. Although the $60-\mathrm{GHz}$ band enjoys a

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relaxed maximum signal power constraint of 10 W , the signal attenuation caused by path loss in the band is significantly higher than that in the low- GHz region [2]. To compensate for the path losses, an electronically steered narrow beam is required to focus the signal power in the desired direction [3]. The beam of a phased array antenna can be electrically steered to the desired radiation direction by progressively varying the phase of the signals feeding the array elements [4]. A large number of phase shifters are often required to produce the required progressive shifts, as the number of antenna elements should be large enough for the desired beam angle resolution [5]. Deep submicrometer CMOS technology is considered as a promising candidate for implementation of phased-array transceivers as it offers low fabrication cost, a high level of integration, and high-speed transistors required for operation at mm-wave frequencies.
Phase shifters can be divided into two categories, namely, active and passive phase shifters. Active phase shifters are usually constructed by summing two perpendicular current vectors with varying ratios allowing for different phase shifts to be generated [6], [7]. The power consumption of active phase shifters is the main concern for using them in phasedarray systems when a large number of antennas elements are required specially for portable battery-powered devices. In addition, the nonlinearity and the noise introduced by the transistors degrade the performance of the active phase shifters [8], [9].

Passive phase shifters can be categorically divided in the following three groups: switched-type, reflection-type, and transmission line phase shifters. The switched-type phase shifters offer a wide yet noncontinuous phase shift range. The application of these phase shifters in mm-wave range is limited by the high switching losses of the transistors at these frequencies. In addition, the junction capacitances of the MOS switch in OFF state degrade the switch isolation and increase the phase shift errors [10]. The reflection-type phase shifters provide continuous phase shift. However, they are typically using couplers or circulators that often occupy large die area and introduce significant losses at mm-wave frequencies [11]-[13]. Vector modulator-based phase shifters exhibit low dynamic range and require several control voltages. In addition, their realization requires additional digital-to-analog converters, which increase the size and consume considerable dc power. The phase error of these phase shifters is more significant because of variable


Fig. 1. (a) General network. (b) Traditionally used cell. (c) Proposed cell for artificial transmission line phase shifters.
gain amplifier (VGA) weight variation [14]. The transmission line-based phase shifters have zero dc power consumption and offer large dynamic range [15], [16]. However, the line-based phase shifters have two main drawbacks. First, they have a limited phase shift range, which is defined by the varactor capacitance range achievable at mm-wave frequencies. In addition, the degrading quality factor of these varactors is also reducing the phase shift range. Second, it is difficult to achieve a proper matching for the entire phase shift range, as the characteristic impedance of transmission line varies with the varactor value.

In this paper, a solution is proposed to enhance the phase shift range and minimize the input/output return losses over the entire phase shift range. Traditionally, the artificial transmission line phase shifters [17] are realized as the cascaded connection of T or $\Pi$ cells [see Fig. 1(a)], where series inductors and shunt varactors form a cell of the phase shifter as shown in Fig. 1(b) [18]-[20]. We propose to construct the phase shifter cells on-chip by tuning both the series inductors and the shunt capacitors, as shown in Fig. 1(c). The proposed cell can theoretically produce twice the phase shift range of a conventional cell while preserving the input/output matching over the entire phase range. This tunable inductor is realized using a varactor-loaded transformer.

This paper is organized in the following way. Section II shows how the inductor tuning increases the phase shift range preserving the input matching. It also describes the main parameters of a one-cell phase shifter with inductive tuning. Section III describes the realization of the elements used in the design of considered phase shifters, namely, the transformer and varactors. Section IV describes the experimental results for all basic characteristics of the one-cell phase shifter. Section V describes the experimental phase characteristics of two- and three-cell phase shifters with tunable inductors. Section VI summarizes this paper on these phase shifters and provides some conclusions and plans for future work. Appendix A describes the traditional cell with a permanent inductor. Appendix B describes the parasitic pad capacitance connected with the design of varactors.

## II. Cell With Capacitor and Inductor Tuning

Let us consider first the traditionally used cell with capacitor-only tuning shown in Fig. 1(b). Using the standard


Fig. 2. Forward transmission gain.
methods of microwave circuit analysis [21], one can write the normalized $A B C D$-matrix of this two-port as

$$
\left[\begin{array}{ll}
A & B  \tag{1}\\
C & D
\end{array}\right]=\left[\begin{array}{cc}
1-\omega^{2} L C_{P} & (j \omega L) / z_{0} \\
j \omega C_{P} z_{0}\left(2-\omega^{2} L C_{P}\right) & 1-\omega^{2} L C_{P}
\end{array}\right]
$$

where $z_{0}$ is the characteristic impedance. Considering that the two-port shown in Fig. 1(b) is a symmetric one $(A=D)$ and using the table of two-port S-parameter conversion [17], one can find

$$
\begin{equation*}
S_{11}=S_{22}=\frac{B-C}{A+B+C+D} \tag{2}
\end{equation*}
$$

and

$$
\begin{equation*}
S_{21}=\frac{2}{A+B+C+D} \tag{3}
\end{equation*}
$$

where $S_{11}$ and $S_{22}$ are the input and output reflection coefficients, and $S_{21}$ is the forward transmission coefficient. Then, using (1) and substituting the corresponding parameters in (2) and (3), one obtains that
$S_{11}=\frac{(j \omega L) / z_{0}-j \omega C_{P} z_{0}\left(2-\omega^{2} L C_{P}\right)}{2\left(1-\omega^{2} L C_{P}\right)+j\left[(\omega L) / z_{0}+\omega C_{P} z_{0}\left(2-\omega^{2} L C_{P}\right)\right]}$
and
$S_{21}=\frac{2}{2\left(1-\omega^{2} L C_{P}\right)+j\left[(\omega L) / z_{0}+\omega C_{P} z_{0}\left(2-\omega^{2} L C_{P}\right)\right]}$.

In the following, $S_{11}$ is used for verification of the input matching condition ( $S_{22}$ could be used in a similar way for output matching) and $S_{21}$ is used for evaluation of the phase shifter performance.

Fig. 2 shows the forward transmission gain $\left|S_{21}\right|$ for typical varactor capacitance $C_{P}$ values [19] used in the design of $60-\mathrm{GHz}$ phase shifters. Three different values of the cell inductance $L$ (also used in design) are shown as a parameter. Fig. 3 shows the forward transmission phase for the same range of $C_{P}$ and the same values of $L$. The calculations are done for $z_{0}=50 \Omega$.

Let us consider now some advantages of using the tuning inductor $L_{T}$ and the requirements imposed on tuning by the fact that $L_{T}$ should change simultaneously with $C_{P}$.

When the inductor does not change, the variation of $C_{P}$ changes by matching at the input (or output) of the traditional cell. Using tuning for $L_{T}$, when $C_{P}$ changes, allows one


Fig. 3. Forward transmission phase.


Fig. 4. Inductor values required by matching condition.
to preserve the matching condition, i.e., $S_{11}=S_{22}=0$. Calculating the inductance $L_{T}$ from this condition, one finds that

$$
\begin{equation*}
L_{T}=\frac{2 C_{P} z_{0}^{2}}{1+\omega^{2} C_{P}^{2} z_{0}^{2}} \tag{6}
\end{equation*}
$$

The plot of this function (for 60 GHz ) is shown in Fig. 4. It indicates immediately the difficulty of the approach: if $C_{P}$, for example, changes linearly with the varactor control voltage, then $L_{T}$ should change in a nonlinear fashion.

Yet one can notice that the variation of $C_{P}$ from approximately 14 to 25 fF requires a nearly linear change of $L_{T}$ from 60 to 100 pH (see Fig. 4). This allows to evaluate the increase in the phase shift range achieved by tuning (see Fig. 5). Indeed, when the inductance is constant, one obtains the phase shift of about $12^{\circ}$ for $L=60 \mathrm{pH}$ (the line segment AB ) or about $13^{\circ}$ for $L=100 \mathrm{pH}$ (the segment CD). But when the tuning is used, the network is moving from one phase characteristic to another, which results in the phase shift of about $22^{\circ}$ (projection of EF on the vertical axis).

Preserving matching and increasing the phase shift range are two main advantages of the proposed cell.

Let us consider the circuit in Fig. 6(a) consisting of the transformer loaded by a tunable capacitor $C_{T}$. This circuit can be described by the operational equations

$$
\begin{align*}
V_{P} & =s L_{P} I_{P}+M s I_{S} \\
V_{S} & =M s I_{P}+s L_{S} I_{S} \tag{7}
\end{align*}
$$

where $L_{P}$ and $L_{S}$ are the self-inductance of primary and secondary, and $M$ is the mutual inductance. Adding to (7)


Fig. 5. Increasing phase shift range by inductor tuning.


Fig. 6. Tunable inductance realization. (a) Transformer loaded by tunable capacitor. (b) Phase shifter cell with tunable inductor and capacitors.
the load equation

$$
\begin{equation*}
I_{S}=-s C_{T} V_{S} \tag{8}
\end{equation*}
$$

one can find the input impedance

$$
\begin{align*}
Z_{\text {in }} & =\frac{V_{P}}{I_{P}}=s L_{P}-\frac{C_{T} M^{2} s^{3}}{1+L_{S} C_{T} s^{2}} \\
& =L_{P} s\left(1-\frac{k^{2} C_{T} L_{S} s^{2}}{1+L_{S} C_{T} s^{2}}\right) \tag{9}
\end{align*}
$$

Here, $k=M /\left(L_{P} L_{S}\right)^{1 / 2}$ is the coupling coefficient.
Substituting $s=j \omega$ in (9), one finds that this input impedance is inductive, with inductance

$$
\begin{equation*}
L_{\mathrm{in}}=L_{\mathrm{in}}\left(C_{T}\right)=L_{P}\left(1+\frac{k^{2} C_{T} L_{S} \omega^{2}}{1-C_{T} L_{S} \omega^{2}}\right) \tag{10}
\end{equation*}
$$

One can see that the required increase of $L_{T}$ can be achieved by increasing $C_{T}$ as it was previously discussed. Of course, the condition $C_{T} L_{S} \omega^{2}<1$ should be preserved. Then, the transformer loaded by $C_{T}$ [see Fig. 6(b)] can be used as a tuning inductor.

Substituting (10) in (4) and (5), one can find the basic parameters of this cell

$$
\begin{gather*}
\varphi\left(C_{P}, C_{T}\right)=-\tan ^{-1} \frac{\omega z_{0} C_{P}\left(\frac{L_{\text {in }}}{C_{P} z_{0}^{2}}-\omega^{2} C_{P} L_{\text {in }}+2\right)}{2\left(1-\omega^{2} C_{P} L_{\text {in }}\right)} \\
S_{11}\left(C_{P}, C_{T}\right)=\frac{\left(j \omega L_{\text {in }} / z_{0}\right)-j \omega C_{P} z_{0}\left(2-\omega^{2} L_{\text {in }} C_{P}\right)}{\left\{\begin{array}{l}
2\left(1-\omega^{2} L_{\text {in }} C_{P}\right) \\
+j\left[\left(\omega L_{\text {in }} / z_{0}\right)+\omega C_{P} z_{0}\left(2-\omega^{2} L_{\text {in }} C_{P}\right)\right]
\end{array}\right\}} \tag{12}
\end{gather*}
$$

$$
S_{21}\left(C_{P}, C_{T}\right)=\frac{2}{\left\{\begin{array}{l}
2\left(1-\omega^{2} L_{\text {in }} C_{P}\right)  \tag{13}\\
+j\left[\left(\omega L_{\text {in }} / z_{0}\right)+\omega C_{P} z_{0}\left(2-\omega^{2} L_{\text {in }} C_{P}\right)\right]
\end{array}\right\}}
$$



Fig. 7. (a) Phase shift. (b) Input matching. (c) Insertion loss of one-cell phase shifter.

These basic parameters are represented as the functions of $C_{P}$ and $C_{T}$ plotted in the form of contour lines in Fig. 7.

Fig. 8 shows how to use these diagrams (for simplicity, Fig. 7 and the procedure of Fig. 8 are shown for the frequency of 60 GHz only). Assume that one wants to realize an extended phase characteristic with the input mismatch which is better than -30 dB . One can put the lines marked as -30 dB from the diagram of Fig. 7(b) on the diagram of Fig. 7(a). Then, using the points located on the lines of given phase within the zone limited by the required matching values (they are numbered from 1 to 8 , and denoted in the following plots as the "data" points), one can find the corresponding values of required $C_{P}$ and $C_{T}$.

Finally, using the tuning characteristics of the capacitors $C_{P}\left(V_{\text {Ptune }}\right)$ and $C_{T}\left(V_{\text {Ttune }}\right)$ (see Section III), one can find the


Fig. 8. Superposition of matching requirements on phase characteristics.
TABLE I
Capacitance Values Providing Phase Shift With Input Matching

| Data | $\mathbf{1}$ | $\mathbf{2}$ | $\mathbf{3}$ | $\mathbf{4}$ | $\mathbf{5}$ | $\mathbf{6}$ | $\mathbf{7}$ | $\mathbf{8}$ |
| :---: | :---: | :---: | :---: | :---: | :---: | :---: | :---: | :---: |
| Cp | 20 | 22 | 24 | 28 | 34 | 40 | 48 | 56 |
| $\mathrm{C}_{\mathrm{T}}$ | 40 | 50 | 58 | 64 | 70 | 73 | 74 | 75 |
| $\mathrm{VC}_{\mathrm{P}}$ | -1 | -0.9 | -0.8 | -0.55 | -0.35 | -0.28 | -0.19 | -0.1 |
| $\mathrm{VC}_{\mathrm{T}}$ | -1 | -0.26 | -0.13 | -0.05 | 0 | 0.04 | 0.06 | 0.07 |
| Phase | -40.4 | -44.3 | -48.5 | -60 | -64.7 | -73.6 | -83.1 | -93 |



Fig. 9. Theoretical phase characteristic versus data shown in Table I for one-cell phase shifter.
voltages, which are necessary to apply to the control terminals of the varactors. These results are summarized in Table I.

One can also see that the shape of the curves of equal losses is similar to that of equal mismatch. This means that one will be able, for the considered zone, to provide small losses as well (not exceeding 0.1 dB ).

Similar calculations can be done for other frequencies as well. These theoretical phase results are summarized in Fig. 9.

## III. Practical Realization of Tuning Elements

## A. Tunable Inductor

We remind that the condition $C_{T} L_{S} \omega^{2}<1$ in (10) is very desirable. If we choose that the maximal value of $C_{T}=100 \mathrm{fF}$ and $C_{T} L_{S} \omega^{2}=0.1$, then one can find that, for operation at 60 GHz , the required value of $L_{S}$ is about 70 pH .

The transformer was designed with primary and secondary, including one turn each [see Fig. 10(a)] having an octagonal shape. Then, the primary/secondary was approximated as a ring with an effective diameter of $D_{\text {eff }}$ [see Fig. 10(b)] or with an effective radius $R_{\text {eff }}=D_{\text {eff }} / 2$. If one considers


Fig. 10. (a) On-chip realization. (b) Model for calculation of self-inductance. (c) Model for calculation of coupling coefficient of tunable inductor.
primary/secondary as an ideal metal ring where the magnetic field is completely outside the ring, then [22]

$$
\begin{equation*}
L_{P}=L_{S} \approx \mu_{0} \pi R_{\mathrm{eff}} \tag{14}
\end{equation*}
$$

where $\mu_{0}=4 \pi \cdot 10^{-7} \mathrm{H} / \mathrm{m}$. In the final design [see Fig. 10(c)], we used $D_{P}=D_{S}=30 \mu \mathrm{~m}$ and the linewidth $W_{P}=W_{S}=6 \mu \mathrm{~m}$. This gives $R_{\text {peff }}=R_{\text {seff }}=\left(D_{P}+\right.$ $\left.W_{P}\right) / 2=18 \mu \mathrm{~m}$. Using (14), one finds $L_{P}=L_{S} \approx 71 \mathrm{pH}$.

For calculation of coupling coefficient, the transformer was modeled as two coupled metal rings [see Fig. 10(c)] with equal diameters located in parallel planes with the distance of $d=2.9 \mu \mathrm{~m}$ between them. This distance includes the thickness of $\mathrm{SiO}_{2}$ between metals $M_{8}$ and $M_{9}$ plus $1 / 2$ thickness of $M_{8}$ plus thickness of $M_{9}$. For such an electromagnetic system [23], [24], the mutual inductance $M$ can be calculated as

$$
\begin{equation*}
M=\mu_{0} \sqrt{R_{\mathrm{peff}} R_{\mathrm{seff}}}\left[\left(\frac{2}{m}-m\right) K(m)-\frac{2}{m} E(m)\right] \tag{15}
\end{equation*}
$$

where $m^{2}=\left(4 R_{\text {peff }} R_{\text {seff }}\right) /\left[d^{2}+\left(R_{\text {peff }}+R_{\text {seff }}\right)^{2}\right]$ and $K(m)$ and $E(m)$ are the complete elliptic integrals of the first and second kinds, respectively. The values of these integrals can be found in [25], or by MATLAB using commands ellipticK (m) and ellipticE(m). Using $R_{\text {peff }}=R_{\text {seff }}=18 \mu \mathrm{~m}$ and $d=2.9 \mu \mathrm{~m}$, one finds $m=0.9968$. Then, one finds that $M \approx 52 \mathrm{pH}$. The calculation of the coupling coefficient $k$ in the model shown in Fig. 10(c) assumes that the inductance of an individual ring is also calculated using the assumption that they both are metal wires with $R_{\text {peff }}=R_{\text {seff }}=18 \mu \mathrm{~m}$. Using (15), one finds that with this assumption, $M=52 \mathrm{pH}$. This gives $k=M / \sqrt{L_{p} L_{s}} \approx 0.725$.

Obtained results were verified using a field simulator. Using this tool, the results obtained are $L_{P}=L_{S} \approx 60 \mathrm{pH}$ and $k \approx 0.55$. The results of the calculations and simulation are summarized in Table II.

Comparing the results of simulation and calculations, one can find that the results given by (14) give the values higher than the results of the simulation. The reader can verify that reasonably close results ( $L_{P}=L_{S} \approx 64 \mathrm{pH}$ ) may be obtained

TABLE II
TRANSFORMER PARAMETERS

| Type | Stacked transformer |  |  |  | Planar transformer |  |  |  |
| :--- | :---: | :---: | :---: | :---: | :---: | :---: | :---: | :---: |
| Parameter | $L_{P}$ | $L_{S}$ | $M$ | $k$ | $L_{P}$ | $L_{S}$ | $M$ | $k$ |
| Calculated | 71 | 71 | 52 | 0.72 | 97 | 67 | 39 | 0.49 |
| Simulated | 60 | 60 | 33 | 0.55 | 80 | 52 | 27 | 0.42 |


(a)

(b)

Fig. 11. (a) Top layout view. (b) Circuit diagram of CMOS varactor.
if the inductance of the ring is calculated as

$$
\begin{equation*}
L \approx \mu_{0}\left(\pi-\frac{W}{D_{\mathrm{eff}}}\right) R_{\mathrm{eff}} \tag{16}
\end{equation*}
$$

where $D_{\text {eff }}$ is the effective (average) diameter and $W$ is the metal linewidth. This is a better correction than that proposed in [22]. The planar transformer is considered in Section V.

## B. Tunable Capacitor (Varactor)

A MOS varactor realized in a $65-\mathrm{nm}$ CMOS process is a three-terminal device with four design parameters of width, length, group number, and branch number. The layout of the MOS varactor is similar to that of the MOSFET. Fig. 11(a) shows the top layout view of a $65-\mathrm{nm}$ MOS varactor.
For the cell optimum performance, the drain and the source were connected together (this results in the minimal area) and both were connected to the ground used as a reference voltage [see Fig. 11(b)]. The gate terminal was used as the tuning voltage node.

Two MOS varactors of different sizes were implemented on chip to use them in the proposed phase shifter. The data for their width, length, the number of groups, and the number of branches are given in Fig. 12. After deembedding pad capacitance (see Appendix B), the experimental intrinsic capacitances of the varactors were obtained. Both the simulated and measured $C-V$ characteristics are shown in Fig. 12. The measured characteristics preserve the same range of capacitor values as simulated characteristics, yet the shape of measured characteristics is different; this results in a different shape of the measured phase characteristics. Possible sources of error in the measurement could be in the deembedding process of the pad capacitors, where the effect of traces connecting the pads to the varactor is not deembedded.

## IV. Cell With Tunable Inductance: Experiment

Fig. 13(a) shows the schematic of the proposed phase shifter cell, including bias and tuning circuits. The tuning capacitor $C_{T}$ was connected to the transformer secondary realized in


Fig. 12. Simulated and measured test varactors. (a) $L=350 \mathrm{~nm}$, $W=700 \mathrm{~nm}, \mathrm{Gr}=1$, and $\mathrm{Br}=17$. (b) $L=200 \mathrm{~nm}, W=500 \mathrm{~nm}$, $\mathrm{Gr}=1$, and $\mathrm{Br}=45$.

(b)

Fig. 13. (a) Circuit diagram. (b) Microphotograph of fabricated one-cell phase shifter.
the second from the top metal. The primary connected in the path of the signal was realized using the top metal (having higher conductance) to provide less insertion loss. The chip microphotograph is shown in Fig. 13(b), and the chip size is $120 \mu \mathrm{~m} \times 130 \mu \mathrm{~m}$ excluding pads.

The varactor capacitors, $C_{P}$ and $C_{T}$, were tuned by two independent voltages. The values of these voltages for each test point are given in Table II, which were obtained for acceptable matching, minimum loss, and maximum phase shift range conditions.

On-wafer S-parameter measurements in the $57-64-\mathrm{GHz}$ range were carried out using vector network analyzer and $110-\mathrm{GHz}$ Cascade Infinity probes.


Fig. 14. Measured and simulated (a) phase characteristic and (b) input reflection and forward transmission coefficients versus data shown in Table III for one-cell phase shifter.

The experimental phase of a single-cell phase shifter is plotted in Fig. 14(a). One can see that the experimental phase shift is about $45^{\circ}$ at 60 GHz . The initial point of the experimental characteristics is shifted down by $-20^{\circ}$; this may be explained by the influence of input and output pad capacitances (about 20 fF each).
Fig. 14(b) shows the experimental reflection and forward transmission coefficients, i.e., it indicates insertion and transmission losses, which occur when the signal passes through the cell.

## V. Multicell Transmission Line Phase Shifters With Tunable Inductances: Experiment

Let us take one of the cells in the cascaded connection shown in Fig. 1(a) and split the series impedance (we are using here the notation $Z_{T}$ instead of $Z_{S}$ ) into two parts [see Fig. 15(a)]. Let the parameters of the cell be chosen so that the impedance looking into input and output terminals of the cell is equal to $z_{0}$ when the cell is connected between the source with the impedance $z_{0}$ and the load equal to $z_{0}$.

Then, it is easy to see that this condition of matching will not change if we cut the wire between two impedances of $Z_{T} / 2$ in the network of Fig. 15(a) and insert it in this cut two back-to-back circuits [see Fig. 15(b)]. Each of these circuits represents half of the cell, and the impedance seen to any side from the point between these circuits is $z_{0}$. Then, the


Fig. 15. Circuit diagrams for derivation of transfer function for single-cell to multiple-cell phase shifters. (a) Generic single-cell phase shifter. (b) Two cascaded single-cell phase shifters. (c) Generic two-cell phase shifter. (d) Two-cell phase shifter with variable inductors and capacitors. (e) Three-cell phase shifter with variable inductors and capacitors.

TABLE III
Capacitors Voltages Values for Test Points on the Plots

| Data | $\mathbf{1}$ | $\mathbf{2}$ | $\mathbf{3}$ | $\mathbf{4}$ | $\mathbf{5}$ | $\mathbf{6}$ | $\mathbf{7}$ | $\mathbf{8}$ |
| :---: | :---: | :---: | :---: | :---: | :---: | :---: | :---: | :---: |
| $\mathrm{VC}_{\mathrm{P}}$ | -1 | -0.9 | -0.8 | -0.55 | -0.35 | -0.28 | -0.19 | -0.1 |
| $\mathrm{VC}_{\mathrm{T}}$ | -1 | -0.26 | -0.13 | -0.05 | 0 | 0.04 | 0.06 | 0.07 |

transfer function

$$
\begin{equation*}
\frac{e_{2}}{e_{1}}=\frac{e_{3}}{e_{2}}=T(s)=e^{-\phi}=e^{-\alpha} \cdot e^{-\beta} \tag{17}
\end{equation*}
$$

where $\alpha$ is the attenuation and $\beta$ is the phase shift [26]. Now, the transfer function

$$
\begin{equation*}
\frac{e_{3}}{e_{1}}=T^{2}(s)=e^{-2 \phi}=e^{-2 \alpha} \cdot e^{-2 \beta} \tag{18}
\end{equation*}
$$

i.e., in the network shown in Fig. 15(b), the phase shift will be two times more in the network shown in Fig. 15(a).

Now, one can recombine impedances for the network of Fig. 15(b) and obtain the network shown in Fig. 15(c). Finally, returning back to inductors and capacitors, one obtains the circuit shown in Fig. 15(c). This is the circuit of a two-cell shifter.

If the procedure of cut and insert is applied once more to the midpoint of the network shown in Fig. 15(b) (that one which has the voltage $e_{2}$ ), then, after recombining and substitution of capacitors and inductors, one obtains the circuit of a three-cell phase shifter shown in Fig. 15(e).

These two- and three-cell phase shifters have been implemented as the experimental examples of multicell transmission line phase shifters with tunable inductances. We are providing the experimental results for both shifters in the following.

## A. Two-Cell Phase Shifter

As discussed earlier, the proposed one-cell phase shifter provided a $45^{\circ}$ phase shift. It follows from the previous discussion that the two-cell phase shifter obtained by cascading of two one-inductor cells can achieve a phase control range of $90^{\circ}$. The capacitor $2 C_{P}$ [see Fig. 15(d)] is realized using the parallel connection of two similar varactors. They are controlled using the same voltages for $C_{P}$ and $C_{T}$ as given in Table III.

The layout of inductors for a two-cell phase shifter chip [see Fig. 16(a)] deserves some comments. We used here


Fig. 16. (a) Microphotograph. (b) Traditional and meandering transformer layout of fabricated two-cell phase shifter.
what we called "meandering layout." The comparison [see Fig. 16(b)] of ordinary and meandering layouts clearly indicates that the last layout provides shorter interinductance connections. Also, since the second inductor is placed further from the first one, then the coupling between two neighbor inductors has been reduced.

This layout also results in a more compact chip (both dimensions are used) and provides some savings in the chip area; the chip size shown in Fig. 16(a) is $170 \mu \mathrm{~m} \times 230 \mu \mathrm{~m}$ excluding the pads.

Then, the S-parameter measurements were conducted in the frequency range from 57 to 64 GHz . The results of these measurements are shown in Fig. 17. These results illustrate that the phase shift range of $92^{\circ}$ has been achieved which is, indeed, approximately two times larger than the range of the single-cell phase shifter. The loss of the two-cell phase shifter varies from 4 to 7 dB at 60 GHz . This variation could be, in the future work, modified and flattened using a simple VGA after this phase shifter.

## B. Three-Cell Phase Shifter

One new element was tried in design and manufacturing of the three-cell phase shifter. It was a planar transformer [see Fig. 18(a)] with primary and secondary located on the same plane and using the top metal (M9) for realization. The electromagnetic parameters of this transformer (see in the following) were close to that of the stacked-up transformer used in the previous two designs. The purpose of this design was to verify the influence of secondary resistance on the circuit performance. We did not find any definitive answer; the performance of the phase shifter very weakly depends on the transformer type.

The top metal was chosen for both primary and secondary inductors, which is the thickest metal layer with a low sheet resistance in $65-\mathrm{nm}$ CMOS technology. The design procedure for this transformer is similar to that outlined in Section III-A. The planar transformer is designed with one turn primary and one turn secondary, both of octagonal shape [see Fig. 18(a)]. To calculate their size, they were approximated as two rings with the diameter of $D_{p}=45 \mu \mathrm{~m}$ and $D_{s}=30 \mu \mathrm{~m}$, and with the linewidth of $W_{p}=W_{s}=4 \mu \mathrm{~m}$. The mutual inductance $M$ can be calculated using the result in (15) for $d=0$,


Fig. 17. Measured and simulated (a) phase shift and (b) forward transmission and input reflection coefficients of the two-cell phase shifter.


Fig. 18. (a) Planar transformer realization. (b) Microphotograph of fabricated three-cell phase shifter.
as the primary and secondary are in the same plane now. Using $R_{\text {peff }}=24.5 \mu \mathrm{~m}$ and $R_{\text {seff }}=17 \mu \mathrm{~m}$, one finds $m=0.9835$ and $M \approx 39.4 \mathrm{pH}$. To calculate the coupling coefficient $k$, the primary and secondary inductors are approximated as $L_{p}=97 \mathrm{pH}$ and $L_{s}=67 \mathrm{pH}$. Then, one finds that $k=M /\left(L_{P} L_{S}\right)^{1 / 2} \approx 0.49$.

More exact values have been obtained using the field simulator with the results of $L_{p}=80 \mathrm{pH}, L_{s}=52 \mathrm{pH}$, and $k \approx 0.42$.

The layout of inductors in the three-cell phase shifter shown in Fig. 18(b) is also employing the same meandering technique as the two-cell phase shifter, and the chip size in Fig. 18(b) is $230 \mu \mathrm{~m} \times 180 \mu \mathrm{~m}$ excluding the pads.


Fig. 19. Measured and simulated (a) phase shift and (b) forward transmission and input reflection coefficients of three-cell phase shifter characteristics.

The circuit was tested using the same voltages on varactors, as shown in Table III. The S-parameter measurements for this shifter were also conducted in the frequency range of $57-64 \mathrm{GHz}$. The results of these measurements are shown in Fig. 19. One can see that the phase shift range of $133^{\circ}$ has been achieved. It is approximately three times larger than the shift range of the single cell. The loss of the three-cell phase shifter varies from 5.7 to 9.9 dB at 60 GHz .

## VI. Conclusion and Discussion

A novel phase-shifter structure was proposed to increase the phase shift range in comparison with a traditional varactor loaded transmission line shifter. The proposed phase shifter is employing tunable elements for both inductors and capacitors. Therefore, a less number of cells are required in the cascaded cell connection to cover the entire desirable phase shift range which eventually leads to a smaller chip area. In the proposed phase shifter, one may achieve the control of inductors and capacitors simultaneously to preserve the line characteristic impedance.

The manufactured and tested one-cell phase shifter has a $45^{\circ}$ phase shift range which is almost twice the shift range of the traditional $\pi$-cell. The proposed two- and three-cell continuous phase shifters also have been designed, fabricated, and tested in $65-\mathrm{nm}$ CMOS technology. Measurement results confirmed the appropriate phase shift range improvement in


Fig. 20. Simulated and measured (a) S-parameters, (b) phase shift, and (c) group delay of three-cell phase shifter in four phase shifting states.
comparison with the shifters based on traditional cells. Fig. 20 shows the simulated and measured S parameters, phase shift, and group delays of the three-cell phase shifter in four different phase-shifting states. The group delay results indicate that an average group delay deviation is 1.97 ps over $57-64 \mathrm{GHz}$. Because the phase shifter is constructed based on a transmission line structure, it is considered as a true time delay phase shifter, as the group delay remains relatively constant within the $57-64-\mathrm{GHz}$ band. Fig. 21 shows the output power of the main harmonic and the third harmonic as a function of input power. Based on the plot, the simulated 1-dB compression point and IIP3 of the phase shifter is 11 dBm and 24 dB for phase shifting state of $\mathrm{VCp}=-0.1 \mathrm{~V}$ and $\mathrm{VCT}=0 \mathrm{~V}$, respectively.


Fig. 21. Simulated P1dB and IIP3 for $\mathrm{VCp}=-0.1 \mathrm{~V}$ and $\mathrm{VCT}=0 \mathrm{~V}$ phase shifting state.


Fig. 22. (a) Planar inductor realization. (b) Microphotograph. (c) Circuit diagram. (d) Measured phase shift of fabricated traditional phase shifter with fixed inductor.

Table IV summarizes and compares the performance parameters of the phase shifter proposed in this paper with those of the recently published mm-wave active [6]-[9], [32] and passive [11]-[13], [15], [19], [28]-[31] phase shifters, all designed in different CMOS technologies. To the best of our knowledge, the proposed continuous phase shifter achieves the highest phase shift range per area among the mm-wave transmission line and switch-type phase shifters reported to date.

TABLE IV
Comparison With Other Millimeter-Wave Phase Shifters

| Ref. | Principle | Frequency (GHz) | Process | Phase range / Resolution | Average Gain (dB) | $\begin{gathered} \text { S11/S22 } \\ (\mathrm{dB}) \\ \hline \end{gathered}$ | $\begin{gathered} \text { Area } \\ \left(\mathrm{mm}^{2}\right) \end{gathered}$ | $\begin{aligned} & \text { Power } \\ & (\mathrm{mW}) \end{aligned}$ | Phase Shifter/True Time Delay |
| :---: | :---: | :---: | :---: | :---: | :---: | :---: | :---: | :---: | :---: |
| [6] | Vector Modulator with Active Switches / 2 bit | 75-110 | $\begin{gathered} 28 \mathrm{~nm} \\ \text { CMOS } \end{gathered}$ | $270^{\circ} / 90^{\circ}$ | 1.5 | -20/-9 | 0.565 | 122.9 | Phase Shifter |
| [7] | Vector Modulator /4 bit | 57-64 | 130 nm <br> CMOS | $360^{\circ} / 45^{\circ}$ | -1 | * | 7 | 72 | Phase Shifter |
| [8] | Vector Modulator Switched Control /4 bit | 15-26 | $\begin{aligned} & 130 \mathrm{~nm} \\ & \text { CMOS } \end{aligned}$ | $360^{\circ} / 45^{\circ}$ | -4.6 | -10/-10 | 0.14 | 11.7 | Phase Shifter |
| [9] | Vector Sum with VGA | 40-75 | $\begin{aligned} & 90 \mathrm{~nm} \\ & \text { CMOS } \end{aligned}$ | $360 \%$ cont. | -18 | -5/-10 | 0.4 | 30 | Phase Shifter |
| [11] | RTPS/5 bit | 57-64 | $\begin{gathered} \hline 65 \mathrm{~nm} \\ \text { CMOS } \\ \hline \end{gathered}$ | $180^{\circ} / 11.25^{\circ}$ | -6 | -10/-10 | 0.18 | 0 | True Time Delay |
| [12] | RTPS | 50-65 | 90nm CMOS | $90^{\circ} /$ cont. | -6.25 | -12/-12 | 0.08 | 0 | True Time Delay |
| [13] | RTPS/3bit | 54-66 | $\begin{gathered} 65 \mathrm{~nm} \\ \text { CMOS } \end{gathered}$ | $90^{\circ} / 11.25^{\circ}$ | -5.7 | -12 | 0.034 | 0 | True Time Delay |
| [15] | Differential Varactor Loaded T-Line /4bit | 55-65 | $\begin{gathered} 65 \mathrm{~nm} \\ \text { CMOS } \end{gathered}$ | $180^{\circ} / 22.5^{\circ}$ | -9.4 | -10/-10 | 0.2 | 0 | True Time Delay |
| [19] | Varactor Loaded TLine/ 8bit | 55-65 | $\begin{gathered} 90 \mathrm{~nm} \\ \text { CMOS } \end{gathered}$ | $180^{\circ} / 22.1^{\circ}$ | $-6.7^{* *}$ | -16/-20** | 0.1 | 0 | True Time Delay |
| [28] | RTPS | 60 | $\begin{gathered} 65 \mathrm{~nm} \\ \text { CMOS } \end{gathered}$ | $180^{\circ}$ | -6.65 | -9 | 0.031 | 0 | True Time Delay |
| [29] | RTPS+ Transformerbased Multi-Resonance Load | 62 | 130 nm BiCMO S | $367^{\circ}$ | $\begin{aligned} & -6.95 / \\ & -9.95 \end{aligned}$ | -10.4 | 0.16 | 0 | True Time Delay |
| [30] | Switch type | 57-64 | 90 nm CMOS | $360^{\circ} / 22.5^{\circ}$ | -18 | - | 0.34 | 0 | Phase Shifter |
| [31] | Switch type | 57-65 | $\begin{gathered} 40 \mathrm{~nm} \\ \text { CMOS } \end{gathered}$ | $360 \% 11.25^{\circ}$ | -20.9 | - | 0.34 | 0 | Phase Shifter |
| [32] | programmable weighted I/Q paths+ VGAs | 61 | $\begin{gathered} 65 \mathrm{~nm} \\ \text { CMOS } \end{gathered}$ | $360^{\circ} / 22.5^{\circ}$ | 7.7 | -10 | 1.6 | 156 | Phase Shifter |
| This work | 3-Cell Varactor Loaded T-Line with Tunable Inductor | 57-64 | $\begin{aligned} & \text { 65nm } \\ & \text { CMOS } \end{aligned}$ | 133 $/$ cont. | -7.8 | -10/-10 | 0.041 | 0 | True Time Delay |

* Not Reported.
**Simulation results were reported.

The major sources of the loss in the network are the losses of on-chip transformers and varactors (particularly transmission line's shunt varactors). The primary and secondary windings of on-chip transformers exhibit a quality factor ranging between 10 and 21 because of metal and substrate losses. Although the quality factor of an inductive element such as inductors and transformers is often higher in mm-wave frequencies than in low- GHz frequencies, they still contribute significantly to the loss of the network. On the other hand, varactors or on-chip capacitors' quality factor significantly degrades as the frequency increases into mm -wave regime accounting for a significant portion of the overall losses. Further work is required to investigate the influence of varactor mismatch on the shifter characteristics. This will help to create the control of tuning capacitors and inductors from one control voltage. Further work will also be required to improve the transmission characteristics of the proposed cell and multicell shifters.

## Appendix A

Phase Shifter With Fixed Inductor
A traditional single-cell phase shifter was also designed, manufactured in the same $65-\mathrm{nm}$ CMOS technology, and
then tested in $57-64-\mathrm{GHz}$ band. This cell (see Fig. 22) consists of an octagonal-shaped fixed inductor $L_{p}$ and two varactors $C_{p}$.

The inductance was calculated [27] as

$$
\begin{equation*}
L_{p}=\frac{K_{1} \mu_{0}}{2} \frac{\left(D_{\mathrm{in}}+D_{\mathrm{out}}\right)^{2}}{\left(D_{\mathrm{in}}+D_{\mathrm{out}}\right)+K_{2}\left(D_{\mathrm{out}}-D_{\mathrm{in}}\right)} \tag{19}
\end{equation*}
$$

where $\mu_{0}=4 \pi \cdot 10^{-7} \mathrm{H} / \mathrm{m}$, and, for octagonal shape, $K_{1}=2.25$ and $K_{2}=3.55$. Using $D_{\text {in }}=30 \mu \mathrm{~m}$ and $D_{\text {out }}=42 \mu \mathrm{~m}$, one finds that $L_{p}=64 \mathrm{pH}$. The field simulated value is 55 pH .

The chip die photograph [see Fig. 22(c)] shows that the limitation on minimum distance between input and output results in the long connection lines. They are comparable in size with an inductor. These lines should be deembedded in the interpretation of measurement results.

The control voltage on varactors was swept from -1 to +1 V . The measured phase shift range of this cell is plotted in Fig. 22(d). The phase shift is approximately $25^{\circ}$. We remind that in the proposed cell, this shift is about $45^{\circ}$, i.e., we have about $80 \%$ increase in comparison with the traditional cell.

(a)

(b)

Fig. 23. (a) Microphotograph of tested varactor. (b) Measured capacitance of bond pad.

## Appendix B <br> Varactor Test Chip

The micrograph of the varactor test structure is shown in Fig. 23(a). Because the test pad size is comparable with the size of the varactor, the pad capacitance should be considered in the measurements. Then, a separate pad was placed on the chip as well; its measured capacitance of $17-20 \mathrm{fF}$ is plotted in Fig. 23(b). This capacitance value was deembedded in all measurements on varactors.

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